

Title of the Invention

NEUTRAL BEAM PROCESSING APPARATUS AND METHOD

Inventors

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TITLE OF THE INVENTION: NEUTRAL BEAM PROCESSING
APPARATUS AND METHOD

BACKGROUND OF THE INVENTION:

5 <Field of the Invention>

The present invention relates to a neutral beam processing apparatus and method and, more particularly, a neutral beam processing apparatus and method suitable for performing an etching process by
10 irradiating an object to be processed with a neutral beam, and the like.

<Related Background Art>

One of processing apparatuses using a neutral beam is a neutral beam processing apparatus for performing
15 a process such as etching by irradiating an object to be processed such as a substrate with a neutral beam. A conventionally known neutral beam processing apparatus of this kind is disclosed in, for example, Japanese application patent laid-open publication No.
20 Hei 7-193047. The neutral beam processing apparatus employs the configuration using a retarding electrode as charged particle separating means. In the case of converting an ion beam pulled out from an ion source to a neutral beam and irradiating an object to be
25 processed with only the neutral beam, the charged

particle separating means separates the neutral beam
obtained by a charge exchanging reaction between a
part of the ion beam and a neutral gas from the
charged particle. The retarding electrode is a multi-
5 aperture electrode having a number of small apertures
for passing the neutral beam. By applying a
predetermined potential to the multi-aperture
electrode, while ions or electrons as the charged
particles are electrostatically removed by repulsion,
10 a neutral beam having no charge is allowed to pass.

The publication also discloses another charged
particle separating means for magnetically separating
electrons in charged particles from a neutral beam by
applying a transverse magnetic field to the surface by
15 a permanent magnet disposed on a side of an object to
be processed and electrostatically separating ions in
the charged particles from the neutral beam by
applying a positive potential to a supporting stand
for supporting the process object.

20 In the neutral beam processing apparatus, in order
to process a larger object and shorten processing time,
it is demanded to enlarge the diameter of a neutral
beam to be applied on the object to be processed and
to increase the capacity of the neutral beam. Moreover,
25 it is requested to enlarge the diameter and increase

the capacity while improving the quality of the neutral beam. That is, small divergence of the neutral beam and small variations in energy are requested.

According to the conventional techniques, for the following reasons, it is limited to enlarge the diameter and increase the capacity of a neutral beam while suppressing divergence of the neutral beam, removing surely the charged particles and reducing variations in energy.

Specifically, in the former one of the above conventional techniques, to achieve good quality of the neutral beam applied to the object to be processed, a retarding electrode has to be constructed by at least three multi-aperture electrodes as will be described hereinbelow. That is, the retarding electrode has to be constructed by a reference electrode to suppress divergence of a neutral beam and to reduce variations in energy, an ion eliminating electrode to eliminate ions, to which a positive potential with respect to the reference electrode is applied, and an electron eliminating electrode to eliminate electrons, to which a negative potential with respect to the reference electrode is applied.

The reference electrode is disposed on the ion source side among the three multi-aperture electrodes,

and a predetermined potential is applied to the reference electrode, thereby specifying a space potential between the reference electrode and the pulling-out electrode. In the case where a gradient occurs in the space potential, for example, when the space potential is specified by the ion eliminating electrode set at a positive potential higher than the potential of the reference electrode and the pulling-out electrode in a state where there is no reference electrode, a gradient (potential barrier) occurs in the space potential between the pulling-out electrode and the ion eliminating electrode. An ion beam before conversion to a neutral beam largely diverges and the energy varies largely. In order to flatten the space potential in the neutralization area in which the ion beam is converted to the neutral beam, the following configuration is employed. The reference electrode is provided to the ion source side more than the ion eliminating electrode, and the reference electrode is set at a predetermined potential lower than the potential of the ion eliminating electrode, thereby flattening the space potential in the neutralization area. By providing the reference electrode to flatten the space potential, the divergence of the neutral beam can be suppressed, and the variations in energy

can be reduced.

The larger the number of electrodes constructing the retarding electrode is, the higher the probability that the neutral beam collides with the electrodes becomes. It therefore causes a problem such that the amount of the neutral beam passing through the retarding electrode and applied to an object to be processed decreases.

It becomes more difficult to maintain a number of apertures formed in a plurality of electrodes at predetermined positions as the diameter of the retarding electrode becomes large. The neutral beam transmittance deteriorates and an decrease in output is caused. Due to the action of flattening the space potential in the neutralization area, the reference electrode inevitably is collided by the ion beam which is not neutralized, so that the reference electrode wears very much.

According to the latter one of the conventional techniques, by applying a parallel magnetic field generated by a permanent magnet disposed on a side of an object to be processed onto the surface of the object, electrons are magnetically separated from the neutral beam. By applying a positive potential to the object, ions are electrostatically separated from the

neutral beam. Consequently, unlike the former
conventional technique, the amount of the neutral beam
applied on the object does not decreases due to the
collision of the neutral beam with the retarding
5 electrode.

By the positive potential applied to the object,
however, a gradient occurs in the space potential in
the neutralization area. Consequently, the ion beam
before conversion to the neutral beam diverges largely
10 and the energy varies largely. As a result, the
neutral beam obtained by converting the ion beam
diverges largely and the energy varies largely.

As the size of an object to be processed increases,
the permanent magnet disposed on a side of the object
15 becomes very large to generate a magnetic field
necessary to separate electrons in the center portion
of the object. Moreover, the difference between the
magnetic field intensity in the center portion of the
object and that in an end portion is conspicuous and
20 an influence on the charged particles becomes non-
uniform. Consequently, the enlargement of the diameter
in the neutral beam processing apparatus is limited.
There are problems such that the apparatus is not
suitable for a process on an object which is easily
25 influenced by a magnetic field such as a magnetic

device since the magnetic field is generated on the surface of the object, and is not suitable for a process on an object of which surface is made of an insulator since ions are removed by applying a
5 predetermined positive potential to the object.

As described above, in the conventional techniques, there is a limit of increase in the diameter and capacity of the neutral beam while suppressing the divergence of the neutral beam applied on the object
10 to be processed, removing surely the charged particles and reducing the variations in energy.

SUMMARY OF THE INVENTION:

An object of the invention is to provide a
15 neutral beam processing apparatus and method using a neutral beam having an enlarged diameter and an increased capacity while suppressing divergence of the neutral beam, removing surely the charged particles and reducing variations in energy.

20 In order to achieve the object, according to the invention, as a first means, there is provided a neutral beam processing apparatus having: an ion source; an ion pulling-out electrode for pulling out ions from the ion source and generating an ion beam; a
25 neutralization cell for neutralizing and converting

the ion beam pulled out by the ion pulling-out
electrode in atmosphere of a neutral gas to a neutral
beam; charged particle separating means for separating
charged particles from the neutral beam in the
5 neutralization cell and allowing a neutral beam to
pass; and a process cell disposed adjacent to the
neutralization cell, for housing an object to be
processed on a propagation path of the neutral beam
passed through the charged particle separating means,
10 wherein the charged particle separating means includes
a multi-aperture electrode having a plurality of
apertures through which the neutral beam passes, and a
plurality of lines of magnets dispersively disposed
adjacent to the multi-aperture electrode, for
15 generating a multi-pole magnetic field near the multi-
aperture electrode.

According to the invention, as a second means,
there is also provided a neutral beam processing
apparatus having: an ion source; an ion pulling-out
20 electrode for pulling out ions from the ion source and
generating an ion beam; a neutralization cell for
neutralizing and converting the ion beam pulled out by
the ion pulling-out electrode in atmosphere of a
neutral gas to a neutral beam; charged particle
25 separating means for separating charged particles from

the neutral beam in the neutralization cell and allowing a neutral beam to pass; and a process cell disposed adjacent to the neutralization cell, for housing an object to be processed on a propagation path of the neutral beam passed through the charged particle separating means, wherein the charged particle separating means includes a multi-aperture electrode to which a positive potential with respect to a neutralization cell wall defining the neutralization cell is applied and which has a plurality of apertures through which the neutral beam passes, a plurality of lines of magnets dispersively disposed adjacent to the multi-aperture electrode, for generating a multi-pole magnetic field near the multi-aperture electrode, and a conductive member which is disposed in a magnetic pole portion of the multi-pole magnetic field in the neutralization cell and to which a negative potential with respect to the multi-aperture electrode is applied.

Any of the following elements can be added to the configuration of the neutral beam processing apparatus.

(1) The plurality of magnet lines also serve as the conductive member.

(2) The plurality of magnet lines are disposed so as to face the conductive member over the multi-

aperture electrode.

(3) Potential difference adjusting means for making a potential difference between a neutralization cell wall defining the neutralization cell and the
5 conductive member may also be provided.

(4) Electron replenishing means for supplying or generating electrons in the neutralization cell may also be provided.

(5) According to the invention, as a second
10 means, there is also provided, as a third means, a neutral beam processing apparatus comprising: an ion source, an ion pulling-out electrode for pulling out ions from the ion source and generating an ion beam, a neutralization cell for neutralizing and converting
15 the ion beam pulled out by the ion pulling-out electrode in atmosphere of a neutral gas to a neutral beam, charged particle separating means for separating charged particles from the neutral beam in the neutralization cell and allowing a neutral beam to
20 pass, and a process cell disposed adjacent to the neutralization cell, for housing an object to be processed on a propagation path of the neutral beam passed through the charged particle separating means, wherein, to a process cell wall for defining the
25 process cell, a mean for giving a negative potential

to a plasma generation cell wall for defining the ion source is provided, and to the plasma generation cell wall, a mean for giving a negative potential to a neutralization cell wall for defining the neutralization cell is provided.

The invention also provides a neutral beam processing method comprising the steps of: pulling out ions from an ion source to generate an ion beam; converting the ion beam into a neutral beam in a neutralization cell; separating and removing ions from charged particles existing in the neutral beam by disposing a multi-aperture electrode on an outlet side of the neutralization cell; generating a multi-pole magnetic field around the multi-aperture electrode by disposing a plurality of magnets near the multi-aperture electrode; separating and removing electrons from charged particles existing in the neutral beam by the multi-pole magnetic field; and irradiating an object to be processed in a process cell with the neutral beam passed through the multi-aperture electrode.

Further, the invention provides a neutral beam processing method comprising the steps of: pulling out ions from an ion source and introducing the ions as an ion beam into a neutralization cell; generating a

multi-pole magnetic field around a multi-aperture
electrode to which a positive potential with respect
to a neutralization cell wall defining the
neutralization cell is applied by disposing the multi-
5 aperture electrode on an outlet side of the
neutralization cell and disposing a plurality of
magnets near the multi-aperture electrode; converting
the ion beam into a neutral beam in a space potential
area which is flat in a wide range in the
10 neutralization cell and is formed by disposing a
conductive member to which a negative potential with
respect to the multi-aperture electrode is applied in
a magnetic pole portion of the multi-pole magnetic
field in the neutralization cell, separating and
15 removing ions in charged particles included in the
neutral beam by the multi-aperture electrode;
separating and removing electrons in the charged
particles by the multi-pole magnetic field; and
irradiating an object to be processed in a process
20 cell with the neutral beam passed through the multi-
aperture electrode.

Further, according to the present invention, a
neutral beam processing method comprising the steps of
pulling out ions from an ion source and introducing
25 the ions as an ion beam into a neutralization cell,

converting the ion beam into a neutral beam in a
neutralization cell, removing charged particles from
the neutral beam by a charged particle removing means;
and irradiating an object to be processed in a process
5 cell with the neutral beam passed through the charged
particle removing means, wherein, to a process cell
wall for defining the process cell, giving a negative
potential to a plasma generation cell wall for
defining the ion source, and further giving a negative
10 potential to a neutralization cell wall for defining
the neutral cell, thereby the ion beam pulled-out from
the ion source is prevented from reaching to the
process cell.

According to the above stated first means, since
15 the ions in charged particles included in a neutral
beam are separated and removed from the neutral beam
by a multi-aperture electrode, and the electrons are
separated and removed from the neutral beam by a
multi-pole magnetic field generated by a plurality of
20 magnet lines. Consequently, the charged particles can
be removed surely from the neutral beam.

Further, according to the second means, the
transmittance can be increased as compared with the
technique of using a plurality of electrodes as the
25 charged particle separating means, and the capacity of

the neutral beam can be prevented from being decreased.
Thus, the capacity of the neutral beam can be
increased. Further, by increasing the number of magnet
lines with the upsizing of the multi-aperture
5 electrode, the diameter of the neutral beam can be
enlarged. Further, since the positive potential to
repel the ions is applied to the multi-aperture
electrode, a wear due to collision with an ion beam
can be avoided. By providing a conductive member as
10 the charged particle separating means, the magnet line
can be prevented from being irradiated with the ion
beam, so that demagnetization caused by heating the
magnet line can be prevented.

Further, according to the third means, to the
15 process cell wall for defining the process cell, the
negative potential is given to the plasma generation
cell wall for defining the ion source, the ion beam
pulled out from the ion source can be prevented from
centering to the process cell.

20
BRIEF DESCRIPTION OF THE DRAWINGS:

Fig. 1A is a vertical section of a neutral beam
processing apparatus as a first embodiment of the
invention, and Fig. 1B is a characteristic diagram of
25 a space potential of the apparatus shown in Fig. 1A;

Fig. 2A is an enlarged cross section of a main portion of charged particle separating means, and Fig. 2B is a characteristic diagram of a space potential around the charged particle separating means shown in Fig. 2A;

Fig. 3A is a vertical section of a neutral beam processing apparatus as a second embodiment of the invention, and Fig. 3B is a characteristic diagram of a space potential of the apparatus shown in Fig. 3A;

Fig. 4 is an enlarged cross section of a main portion of the apparatus shown in Fig. 3A; and

Fig. 5A is a vertical section of a neutral beam processing apparatus as a third embodiment of the invention, and Fig. 5B is a characteristic diagram of a space potential of the apparatus shown in Fig. 5A.

DETAILED DESCRIPTION OF THE PREFERRED EMBODIMENTS:

A neutral beam processing apparatus and a method of a neutral beam processing of a first embodiment according to the present invention will now be described hereinbelow with reference to the drawings. Fig. 1A is a vertical section showing a general configuration of a neutral beam processing apparatus as the first embodiment of the invention, and Fig. 1B is a characteristic diagram of a space potential of

the apparatus shown in Fig. 1A.

In Fig. 1A, the neutral beam processing apparatus has an ion source for generating a plasma by microwave discharge. In the ion source, a plasma production cell
5 1 is defined by a production cell wall 2, and a waveguide 4 and a gas introducing tube 37 are connected to the production cell wall 2. The plasma production cell 1 has an inner diameter in the vertical direction in Fig. 1A of $\phi 350$ mm and a depth
10 in the lateral direction of 150 mm. For example, the plasma producing cell 1 is formed almost in a bowl shape by the production cell wall 2 made of a non-magnetic material such as stainless steel. The right side of the plasma production cell 1 is open. The
15 waveguide 4 is connected to the center portion on the left side of the production cell wall 2. A microwave introducing window 6 is attached to the inside of the waveguide 4 so as to maintain the air tightness in the plasma production cell 1. A microwave generator (not
20 shown) is connected to the waveguide 4. A microwave having a frequency of 2.45 GHz generated from the microwave generator is introduced through the waveguide 4 and the microwave introducing window 6 into the plasma production cell 1. The gas introducing
25 tube 37 is connected to the production cell wall 2 in

a position lower than the waveguide 4. A specific gas necessary for plasma production, for example, argon gas is introduced into the plasma production cell 1 via the gas introducing tube 37.

5 On the outer periphery side of the production cell wall 2, permanent magnets 5 are lined (permanent magnet line). The permanent magnet line 5 can generate a magnetostatic field having an electron cyclotron resonance field in the plasma production cell 1. The
10 bottom side of the production cell wall 2 is connected to a direct voltage source 36 and a direct voltage of, for example, 600V to 1000V is applied to the production cell wall 2.

 Further, a flange is formed on the open side of
15 the production cell wall 2, and an ion pulling-out electrode for pulling out the ions in the plasma production cell 1 to generate an ion beam is attached to the open side of the production cell wall 2. The ion pulling-out electrode is constructed by a screen
20 electrode 3a, an accelerating electrode 3b, and a decelerating electrode 3c. The screen electrode 3a is disposed on the plasma production cell 1 side, the accelerating electrode 3b is disposed on the right side of the screen electrode 3a, and the decelerating
25 electrode 3a is disposed on the right side of the

accelerating electrode 3b. In each of the screen
electrode 3a, accelerating electrode 3b, and
decelerating electrode 3c, a plurality of apertures
each having a predetermined size are formed at
5 predetermined intervals. In the embodiment, the area
in which the plurality of apertures in the ion
pulling-out electrode are distributed has a size of
 $\phi 300$ mm. Since the positive polarity of the direct
voltage source 36 is connected to the production cell
10 wall 2 and the negative polarity of the direct voltage
source 36 is connected to a process cell wall 15, a
positive potential with respect to the process cell
wall 15 is applied to the production cell wall 2.

A neutralization cell 11 is connected to the open
15 side of the plasma production cell 1 having the above
configuration. The neutralization cell 11 is formed in
an almost cylindrical shape and defined by a
neutralization cell wall 8. A waveguide 12 and a gas
introducing tube 38 are connected to the
20 neutralization cell wall 8.

The neutralization cell wall 8 is formed in a
cylindrical shape having, for example, an inner
diameter of 400 mm and a depth of 350 mm and is made
of a non-magnetic stainless steel. A flange formed at
25 the left end in the axial direction is connected to

the flange formed at the right end of the production cell wall 2 via an insulative spacer 7. A flange formed at the right end in the axial direction is connected to the process cell wall 15. Both the flange and the process cell wall 15 are connected to the ground. The neutralization cell wall 8 is used to enclose an ion beam pulled out from the plasma production cell 1. On the outer periphery of the neutralization cell wall 8, two sets of permanent magnetic lines 9 are arranged in the axial direction (lateral direction) so that the polarities of the magnets in each set are different from each other. Each of the permanent magnet lines 9 is provided to generate a multi-ring cusp field having the electron cyclotron resonance magnetic field in the neutralization cell 11. The permanent magnet line 9 is made of, for example, samarium cobalt (having residual magnetic flux density of about 1.1T) and has a thickness of 8 mm and a length in the magnetization direction of 12 mm.

On the outer periphery of the neutralization cell wall 8, the waveguide 12 is attached in the direction orthogonal to the axial direction of the neutralization cell wall 8. The waveguide 12 is disposed between the two sets of the permanent magnet

lines 9 on the outer periphery of the neutralization
cell wall 8 and introduces a microwave having a
frequency of 2.45 GHz from neighboring magnetic poles
of the multi-ring cusp fields in the neutralization
5 cell wall 8. The permanent magnet lines 9 generate
multi-ring cusp fields and also generate an electron
cyclotron resonance magnetic field corresponding to
the frequency of the microwave. Further, in order to
introduce a microwave and maintain the air tightness
10 in the neutralization cell 11, in a manner similar to
the waveguide 4, the waveguide 12 is provided with a
microwave introducing window 13 made of quartz,
alumina, or the like.

A multi-aperture electrode 32 as an element of the
15 neutralization cell 11 and a process cell 23, which
defines the neutralization cell 11 and the process
cell 23 is attached to the right-side opening of the
neutralization cell wall 8. In the multi-aperture
electrode 32, a plurality of apertures each having a
20 predetermined size are formed as passages of the
neutral beams at predetermined intervals. The positive
polarity of the direct voltage source 33 is connected
to the multi-aperture electrode 32, and a direct
voltage of, for example, 700 V is applied to the
25 multi-aperture electrode 32. Consequently, a positive

potential with respect to the neutralization cell wall
8 having the same potential as that of the process
cell wall 15 is applied to the multi-aperture
electrode 32. In the embodiment, the area in which the
5 plurality of apertures are distributed in the multi-
aperture electrode 32 has a size of $\phi 350$ mm.

A plurality of permanent magnet lines 31 as
magnetic bodies are disposed adjacent to the multi-
aperture electrode 32. Each of the permanent magnetic
10 lines 31 is disposed so that the poles are
perpendicular to the surface of the multi-aperture
electrode 32 and the polarities of neighboring
permanent magnet lines are different from each other.
The permanent magnet lines 31 are fixed to the multi-
15 aperture electrode 32 by using, for example, an
insulating member. By the plurality of permanent
magnetic lines 31, multi-pole magnetic fields 30 are
generated around the multi-aperture electrode 32 in
the neutralization cell 11. The permanent magnet line
20 31 is made of samarium cobalt (having residual
magnetic flux density of about 1.1T) which is a
conductive material, and has a thickness of 4 mm and a
length in the magnetizing direction of 8 mm. The
neighboring permanent magnet lines are set with an
25 interval of 50 to 60 mm. The magnetic field strength

of the multi-pole magnetic field 30 generated by the permanent magnet lines 31 becomes the maximum at about 10 mT in a line segment cd shown in Fig. 2A, drastically decreases with distance from the maximum value position (almost at midpoint between a line segment indicative of a line of magnetic force of the multi-pole magnetic field 30 and the multi-aperture electrode 32). The magnetic field strength is about 3 mT at a position away from the multi-aperture electrode 32 by 50 mm, and is about 1 mT at a position away from the multi-aperture electrode 32 by 80 mm. The line of magnetic force representatively shown as the multi-pole magnetic field 30 has the magnetic field strength of about 1 to 3 mT on the line segment cd. The permanent magnet line 31 is connected to the neutralization cell wall 8 via a conductive member (wire) and connected to the ground so that its potential is the same as that of the neutralization cell wall 8.

The process cell 23 is connected on the right side of the neutralization cell 11. The process cell 23 is a space for housing an object 17 to be processed such as a substrate and for processing the process object 17 with a neutral beam passed through the multi-aperture electrode 32. The process cell 23 is defined

by the process cell wall 15 made of a non-magnetic material such as a stainless steel. A gas introducing tube 39 for introducing a specific gas such as argon or halogen gas into the process cell 23 is connected to the process cell wall 15. The process object 17 is disposed in a position on a propagation path of the neutral beam passed through the multi-aperture electrode 32 so as to be almost orthogonal to the neutral beam and is supported by a supporting stage 16. The supporting stage 16 is connected to the ground in a manner similar to the process cell wall 15.

The neutral beam processing apparatus in the embodiment is constructed as described above. Its action will now be described. First, the process cell 23 is exhausted by using a vacuum pump (not shown) as shown by the arrow, thereby setting the pressure in the process cell 23 to 1×10^{-4} Pa or lower. Subsequently, a gas such as argon gas is supplied from the gas introducing tube 37, 38, or 39 into the plasma production cell 1 to thereby set the pressure in the plasma production cell 1 to 3×10^{-2} Pa to 3×10^{-1} Pa. After that, a microwave of 2.45 GHz is introduced via the waveguide 4.

Consequently, in the plasma producing cell 1, a plasma is generated from the supplied gas with the

microwave. In an area of a magnetic field intensity of, for example, about 87.5 mT at which the cyclotron resonance frequency of the electrons in the plasma and the microwave frequency coincide with each other, the microwave is efficiently absorbed by the electrons in the plasma. A high energy electron generated ionizes the gas, thereby generating a high-density plasma.

At this time, when the production cell wall 2 and the screen 3a in the ion source are set at a positive potential with respect to the neutralization cell wall 8 by the direct voltage source 36, and the accelerating electrode 3b is set at a negative potential with respect to the neutralization cell wall 8, only the ions are pulled out as an ion beam from the high-density plasma in the plasma production cell 1 into the neutralization cell 11. The decelerating electrode 3c is set at the ground potential in a manner similar to the neutralization cell wall 8.

When the ion beam is pulled out into the neutralization cell 11, a part of the ion beam is converted to a neutral beam by a neutralizing action which will be described hereinlater in the neutralization cell 11. The electrons and ions mixedly existing in the neutral beam are separated from the neutral beam by a charged particle separating action

which will be described hereinlater. Only the neutral beam passes through the multi-aperture electrode 32, is led into the process cell 23, and falls onto the process object 17 on the supporting stage 16. In such
5 a manner, a desired neutral beam process such as a neutral beam etching process can be performed on the process object 17. At this time, according to a desired neutral beam process, by introducing a specific gas such as, for example, halogen gas from
10 the gas introducing tube 39 in the case of a neutral beam etching process, the effect on the process can be increased.

The action of neutralizing the ion beam in the neutralization cell 11 will now be described. The
15 pressure in the neutralization cell 11 is set to 3×10^{-2} Pa to 3×10^{-1} Pa by supplying the specific gas such as argon gas from the gas introducing tube 38 into the neutralization cell 11. After that, when the ion beam is introduced into the neutralization cell 11,
20 a part of the ion beam is converted to a neutral beam by a charge exchange reaction with the neutral gas (neutral particles of the specific gas).

In the case of converting the ion beam into the neutral beam, when it is assumed that the permanent
25 magnetic lines 31 are not connected to the ground

together with the neutralization cell wall 8 but are set at the same potential as that of the multi-aperture electrode 32, that is, at a positive potential with respect to the neutralization cell wall 8, as a spatial potential on a line segment ab in Fig. 1A, a spatial potential in the neutralization cell 11 between the decelerating electrode 3c and the multi-aperture electrode 32 is specified by the potentials of the decelerating electrode 3c and the multi-aperture electrode 32. As shown by the broken line (II) in Fig. 1B, the space potential which increases toward the multi-aperture electrode 32 is generated in the neutralization cell 11. In this case, a secondary electron is generated by collision between the ion beam and the neutralization cell wall 8. Even when the secondary electron is supplied to the neutralization cell 11, the electron is easily absorbed by the magnetic poles of the permanent magnet line 31 which is set at the positive potential, and cannot stay long in the neutralization cell 11. Consequently, many ion beams having relatively positive charges and many low-energy ions generated by the charge exchange between the ion beam and the neutral gas exist in the neutralization cell 11. As a result, the ion beam passing through the area of the space potential having

the gradient diverges due to an influence of the potential barrier and is further decelerated, and the kinetic energy decreases. Also in the case where the ion beam is converted to the neutral beam by the charge exchange reaction with the neutral gas in the neutralization cell 11, the neutral beam after the conversion diverges largely, and the energy varies largely.

On the other hand, in the embodiment, the permanent magnetic line 31 is set at the same potential as that of the neutralization cell wall 8, that is, the permanent magnetic line 31 is connected to the ground together with the neutralization cell wall 8. Consequently, the space potential between the decelerating electrode 3c and the permanent magnet line 31 can be specified by the potentials of the decelerating electrode 3c and the neutralization cell wall 8. Therefore, when the ion beam collides with the neutralization cell wall 8, thereby generating the secondary electron, and the secondary electron is supplied to the neutralization cell 11, the secondary electron is not easily absorbed by the magnetic pole of the permanent magnet line 31 but, rather, reflected by a mirror effect of the magnetic pole of the permanent magnet line 31. Consequently, in Fig. 2A, in

the space area A where electrons can easily move and which is wide in the radial and axial directions in the neutralization cell 11, a plasma can be formed by the electrons with the low-energy ions generated in the process of neutralizing the ion beam. By the formation of the plasma, in the space area A which is wide in the radial and axial directions in the neutralization cell 11, as shown by the solid line (I) in Fig. 1B, the space potential is flattened as a potential close to the neutralization cell wall 8. As a result, the ion beam passing through the wide space area A does not diverge. Moreover, the ion beam is not decelerated and the kinetic energy is not decreased. Thus, the neutral beam generated in the wide space area A does not diverge so much in the large-diameter area and variations in energy are suppressed.

The case of using the secondary electrons generated by the collision of the ion beam with the neutralization cell wall 8 in the process of forming the plasma in the space area A and flattening the space potential in the neutralization cell 11 has been described above. This is effective only when the amount of the ion beam is relatively small. Specifically, in the case of introducing an ion beam of a heavier current into the neutralization cell 11

and neutralizing the ion beam to thereby obtain a larger amount of a neutral beam, only with electrons generated secondarily such as secondary electrons, there is a limitation of neutralizing the positive charge of the ion beam to thereby flatten the space potential.

In the embodiment, therefore, as described above, as electron replenishing means for supplying or generating an electron or plasma in the neutralization cell 11, the waveguide 12, gas introducing tube 38, and permanent magnet line 9 are provided to generate the multi-ring cusp magnetic field having the electron cyclotron resonance field in the neutralization cell 11, introduce the microwave from the waveguide 12 into the neutralization cell 11, and generate the plasma in the neutralization cell 11 by the interaction between the microwave and the electron cyclotron resonance field. Since the density of the plasma can be adjusted by the strength of the microwave to be introduced, even when the ion beam introduced into the neutralization cell 11 is of a heavy current, by generating a plasma of a predetermined density according to the heavy current, the space potential can be flattened with reliability as a potential close to the neutralization cell wall 8 as shown by the

solid line (I) in Fig. 1B in the space area A which is wide in the radial and axial directions in the neutralization cell 11. Therefore, the ion beam passing through the space area A does not diverge and is not decelerated, and the kinetic energy does not decrease. Thus, the neutral beam of a large capacity generated by neutralizing the ion beam of the heavy current in the space area A, which does not diverge so much in the large-diameter area with small variations in the energy can be obtained.

Referring now to Figs. 2A and 2B, the action of the charged particle separating means according to the invention will be described. In the embodiment, the charged particle separating means is constructed by the multi-aperture electrode 32 to which a positive potential with respect to the neutralization cell wall 8 is applied and the plurality of magnet lines 31 for generating the multi-pole magnetic field 30 around the multi-aperture electrode 32.

In the case of separating the ion beam and the low-energy ion by using the charged particle separating means, in the embodiment, the multi-aperture electrode 32 is set at a positive potential with respect to the neutralization cell wall 8 by a power source 33. The positive potential is higher than

the positive potential set for the production cell wall 2 and the screen electrode 3a in the ion source. On the other hand, the permanent magnet line 31 is set at the same potential (ground potential) as that of the neutralization cell wall 8. By the setting of the potentials, around the multi-aperture electrode 32 shown by the line segment cd in Fig. 2A, the space potential which increases toward the multi-aperture electrode 32 is generated as shown by the solid line in Fig. 2B.

By the generation of the space potential which sharply increases as the space potential between the permanent magnet line 31 and the multi-aperture electrode 32, ions 25 including the ion beam and the low-energy ion are returned by the potential barrier of the space potential back to the inside of the neutralization cell wall 11 before reaching the multi-aperture electrode 32. The ions 25 cannot pass through the multi-aperture electrode 32 and enter the process cell 23.

An electron 24 having a small Larmor radius due to a magnetic field cannot cross the multi-pole magnetic field 30 generated around the multi-aperture electrode 32 by the permanent magnet line 31 and cannot reach the multi-aperture electrode 32. The electron 24 goes

along the line of magnetic force of the multi-pole
magnetic field 30, collides with the magnetic pole of
the permanent magnet line 31, and vanishes, or is
reflected by the mirror effect. Consequently, the
5 electron 24 cannot pass through the multi-aperture
electrode 32 and enter the process cell 23.

In contrast with the charged particles, the course
of the neutral beam 29 is not deviated by both the
magnetic field and the space potential, and the
10 neutral beam 29 can easily reach the multi-aperture
electrode 32. The neutral beam 29 passes through the
apertures in the multi-aperture electrode 32 at random,
enters the process cell 23, and is applied on the
process object 17.

15 As described above, the charged particle
separating means in the embodiment uses only one
multi-aperture electrode 32. Consequently, as compared
with the conventional technique using the retarding
electrode made by a plurality of multi-aperture
20 electrodes, in the case of enlarging the diameter of
the neutral beam, there is no difficulty to keep a
number of apertures opened in the plurality of
electrodes in predetermined positions, so that the
diameter of the neutral beam can be easily enlarged.
25 Since the number of electrodes is small and the

probability that the neutral beam collides the
electrode is low, the reduction amount of the neutral
beam passing through the electrode and applied on the
process object 17 can be decreased. That is, the
5 neutral beam transmission can be improved. Since the
positive potential to repel ions is applied to the
multi-aperture electrode 32, the multi-aperture
electrode 32 can be prevented from being worn due to
the collision with the ion beam.

10 Further, as compared with the conventional
technique to magnetically separate and remove the
electrons by applying a parallel magnetic field onto
the surface of the object to be processed by the
permanent magnet arranged on the side face of the
15 process object 17, the permanent magnet line 31 for
forming the multi-pole magnetic field 30 is used in
the neutralization cell 11 in the embodiment.
Consequently, the beam diameter can be easily enlarged
by increasing the number of lines of the permanent
20 magnet lines 31 without enlarging the permanent magnet.
Since the magnetic field strength of the multi-pole
magnetic field 30 generated by the permanent magnet
line 31 sharply attenuates with distance from the
permanent magnet line 31, by disposing the process
25 object 17 in a position apart from the permanent

magnet line 31 in the process cell 23, an influence of the magnetic field onto the process object 17 can be eliminated. Even in the case of an object to be processed such as a magnetic device which is easily
5 influenced by the magnetic field, the neutral beam process can be performed with reliability. Since ions are removed by repulsion by the multi-aperture electrode 32, as compared with the conventional technique of removing ions by repulsion by applying
10 the positive potential to the process object 17, even when the process object is an insulator, the neutral beam process can be carried out with reliability.

According to the embodiment, a neutral beam which does not diverge so much in the neutralization cell 11 with small variations in energy and has, moreover, a
15 large diameter and a large capacity can be generated. Further, the neutral beam from which charged particles are separated and removed in the area of the large diameter by the charged particle separating means with
20 reliability can be applied onto the process object 17. Consequently, the process object 17 can be subjected to the neutral beam process using a neutral beam having a large diameter and a large capacity with small variations in energy.

25 In the embodiment, in place of connecting the

permanent magnet line 31 directly to the
neutralization cell wall 8, the permanent magnet line
31 and the neutralization cell wall 8 are connected to
each other via a direct current source. The permanent
5 magnet line 31 can be set at a negative potential with
respect to the neutralization cell wall 8, which is
according to an output voltage of the direct voltage
source.

A second embodiment of the invention will now be
10 described with reference to Figs. 3A and 3B and Fig. 4.
Fig. 3A is a vertical section of a neutral beam
processing apparatus as another embodiment of the
invention. Fig. 3B is a characteristic diagram of the
spatial potential of the apparatus shown in Fig. 3A.
15 Fig. 4 is an enlarged section of a main portion of the
apparatus illustrated in Fig. 3A.

In the another embodiment, three problems of the
foregoing embodiment are solved in the following
manner. The charged particle separating means is
20 constructed by the multi-aperture electrode 32,
permanent magnet line 31, and a plurality of
conductive members 40. The permanent magnet line 31 is
disposed in the process cell 23. The plurality of
conductive members 40 are disposed in the
25 neutralization cell 11 so as to face the permanent

magnet line 31 via the multi-aperture electrode 32. Each of the conductive members 40 is connected to a direct voltage source 35. An insulative spacer 14 is inserted between the neutralization cell wall 8 and
5 the process cell wall 15. The process cell wall 15 is connected to the ground together with the supporting stage 16. A voltage of, for example, -50V is applied from the direct voltage source 36 to the production cell wall 2. A voltage of, for example, -650V is
10 applied from the direct voltage source 34 to the neutralization cell wall 8. A direct voltage of 0 to +30V is applied from the direct voltage source 35 to each of conductive members 40.

Specifically, the foregoing embodiment has the
15 three problems as described below.

(1) Since the permanent magnet line 31 is disposed in the neutralization cell 11, the permanent magnet line 31 is heated by collision with the ion beam and the neutral beam. Depending on the degree of
20 heating, the permanent magnet line 31 may be demagnetized.

(2) Since the neutralization cell wall 8 is at the same potential as the process cell wall 15, the multi-aperture electrode 32 to which the positive
25 potential with respect to the neutralization cell wall

8 is applied to remove the ion beam by repulsion has the positive potential also with respect to the process cell wall 15. Consequently, secondary electrons generated when the process object 15 is irradiated with the neutral beam are electrostatically attracted by the multi-aperture electrode 32. When the surface of the process object 17 is made of an insulating material, positive charges are residual on the surface of the insulating material. The surface of the process object 17 can be therefore charged at a positive potential largely with respect to the process cell wall 15.

(3) In the case where the apparatus is used for an application requiring high-accuracy control on a generation amount of a neutral beam, for example, a case of optimizing a process shape of a process object in a neutral beam etching process, a parameter which can control the neutral beam divergence amount is only the intensity of a microwave guided from the waveguide 12 into the neutralization cell 11 in order to generate a plasma. Consequently, it is difficult to address the requirement depending on the accuracy of the control required.

In contrast, in the another embodiment, the permanent magnet line 31 is disposed in the process

cell 23, the neutralization cell wall 8 is connected to the process cell wall 15 via the insulative spacer 14, the neutralization cell wall 8 is set at a negative potential with respect to the process cell wall 15 by the direct voltage source 34, and the multi-aperture electrode 32 is set at the same ground potential as that of the process cell wall 15. Further, the conductive members 40 are provided for the magnet pole portions of the multi-pole magnetic fields 30 generated in the neutralization cell 11 by the permanent magnet line 31, and the potential of the conductive member 40 is varied with respect to the neutralization cell wall 8 by the direct voltage source 35 as potential difference adjusting means.

Consequently, according to the embodiment, since the permanent magnet line 31 is disposed in the process cell 23, the permanent magnet line 31 is not irradiated with the ion beam. Moreover, the permanent magnet line 31 is positioned behind the multi-aperture electrode 32 and is not therefore also irradiated with the neutral beam. Consequently, the demagnetization due to the heating of the permanent magnet line 31 can be prevented.

According to the embodiment, since the multi-aperture electrode 32 is connected to the ground so as

to be set at the same potential as that of the process
cell wall 15, secondary electrons generated when the
process object 17 is irradiated with the neutral beam
are not electrostatically attracted by the multi-
5 aperture electrode 32 but can return to the surface of
the process object 17. Even when the surface of the
process object 17 is made of an insulating material,
the surface can be prevented from being charged at the
positive potential largely with respect to the process
10 cell wall 15. In this time, since the plasma
generation cell wall 2 for defining the ion source is
established to have the negative potential (-50 V)
according to the direct current source 36, even when
the multi-aperture electrode 32 has the ground
15 potential, the ion beam pulled put from the ion source
can be repelled and removed surely. Although it has
been described in the embodiment that the potential of
the multi-aperture electrode 32 is the same as that of
the process cell wall 15, when they have almost the
20 same potential, similar effects can be produced.

Further, in the embodiment, the conductive members
40 are disposed in the magnet pole portions of the
multi-pole magnetic fields 30 generated in the
neutralization cell 17 by the permanent magnet line 31,
25 and the potential of the conductive member 40 is

varied with respect to the neutralization cell wall 8 by the direct voltage source 35. Consequently, the gradient of the space potential in the neutralization cell 11 can be adjusted.

5 For example, when it is assumed that the voltage across the direct voltage source 35 is 0V, as a space potential on a line segment ab in Fig. 3A, as shown by the solid line (I) in Fig. 3B, the space potential can be flattened in the wide space area A in the
10 neutralization cell 11 as a potential close to the neutralization cell wall 8.

 When a voltage of, for example, +30V is generated across the direct voltage source 35 and a slightly positive potential with respect to the neutralization
15 cell wall 8 is applied to the conductive member 40, as shown by the broken line (II) in Fig. 3B, a space potential which slightly increases toward the multi-aperture electrode 32 in the wide space area A in the neutralization cell 11 can be generated. An ion beam
20 passing through such a space potential diverges slightly, so that the neutral beam generated by converting the ion beam diverges slightly. By controlling the output voltage of the direct voltage source 35, a neutral beam having a desired degree of
25 divergence can be therefore easily obtained.

In the embodiment, as shown in Fig. 4, in the case of separating the electrons 24 from the neutral beam 29, the plurality of permanent magnet lines 31 are disposed around the multi-aperture electrode 32 to generate the multi-pole magnetic fields 30 around the multi-aperture electrode 32, the conductive members 40 to which a negative potential with respect to the multi-aperture electrode 32 is applied are disposed so as to face the permanent magnet line 31 over the multi-aperture electrode 32, and a potential slightly higher than that of the neutralization cell wall 8 is applied to the conductive member 40. Thus, the electrons 24 can be separated from the charged particles existing in the neutral beam 29 by the multi-pole magnetic fields 30 and the conductive members 40.

According to the embodiment, the neutral beam which does not diverge so much in the neutralization cell 11 with small variations in energy and has, moreover, a large diameter and a large capacity can be generated. Further, the process object 17 can be irradiated with the neutral beam from which the charged particles are separated and removed with reliability in the large-diameter area by the charged particle separating means. Consequently, the neutral

beam process using a neutral beam with suppressed divergence and small variations in energy and, moreover, of a large diameter and a large capacity can be performed on the object 17 to be processed.

5 Next, a third embodiment according to the present invention will be explained referring to Fig. 5A and Fig. 5B. Fig. 5A is a vertical section of a neutral beam processing apparatus as a third embodiment of the invention, and Fig. 5B is a characteristic diagram of
10 a space potential of the apparatus shown in Fig. 5A.

 In this third embodiment according to the present invention, the charged particles remove means is constituted by the multi-aperture electrode 32a, 32b, and 32c, and a permanent magnet line 31. The permanent
15 magnet line 31 is arranged in the process cell 23 and adjacent to this at a left side the multi-aperture electrode 32a and at a right side of this multi-aperture electrode 32a the multi-aperture electrode
20 32b and further at a right side of this multi-aperture electrode 32b the multi-aperture electrode 32c are arranged. Further, each of the multi-aperture electrode 32a, 32b, and 32c has a predetermined interval and the plural aperture having a
25 predetermined size are formed. These multi-aperture electrode 32a, 32b, and 32c are connected to the

direct current source 33, the direct current source 50
and the neutralization cell wall 8, respectively. To
the generation cell wall 2 according to the direct
current source 36, for example, the voltage having -
5 100 V is applied, to the neutralization cell wall 8
and the multi-aperture electrode 32c, according to the
direct current source 34, for example, the voltage
having - 700 V is applied, to the multi-aperture
electrode 32b, according to the direct current source
10 50 the voltage having - 900 V is applied, and to the
multi-aperture electrode 32a, according to the direct
current source 33 the voltage having - 5 V degree is
applied, accordingly two problems in the above stated
first embodiment and the above stated second
15 embodiment according to the present invention can be
dissolved.

In concretely, in the above stated two embodiments
according to the present invention, following two
problems occur.

20 (1) In a case the gas in which the negative ion
such as a halogen gas etc. is generated easily is used,
in the neutralization cell 11 much negative ions occur,
the discharged particles remove means in the above
stated two embodiments, namely with respect to the
25 neutralization cell wall 8 by the multi-aperture

electrode 32 and the permanent magnet line 31 which
are given the positive potential, since this negative
ions are not removed, the negative ions enter into the
process cell 23 and the surface of the object to be
5 processed is irradiated.

Since the neutral beam is irradiated to the
surface of the object 17 to be processed, a part of
the secondary electrons becomes the ground potential
and flows into the multi-aperture electrode 32, when
10 the object 17 to be processed is an insulated material,
there is a case that to the surface of the insulated
material the positive potential lefts slightly and the
surface of the object 17 to be processed is charged
with 0.5 - several V to the process cell wall 15.

15 On the other hand, in this embodiment according to
the present invention, according to the direct current
source 50, since the multi-aperture electrode 32b is
given the negative potential than that of the
neutralization cell wall 8, the negative ions which
20 have generated according to this multi-aperture
electrode 32b are repelled and the entering of the
negative ions to the process cell 23 and the
irradiation to the surface of the object to be
processed can be prevented. However, since the neutral
25 beam etc. are irradiated, the entering of the

secondary electrons generated from the multi-aperture electrodes 32a and 32b can not be prevented.

On the other hand, in this embodiment according to the present invention, since the permanent magnet line
5 31 is arranged near to the process cell 23 than the multi-aperture electrodes 32a and 32b, the entering of the secondary electrons generated from the multi-aperture electrodes 32a and 32b can be prevented. As stated in above, in the neutralization processing
10 apparatus of this embodiment according to the present invention, the charged particles can be removed surely from the neutral beam.

Further, according to this embodiment according to the present invention, since the multi-aperture
15 electrodes 32 is given the slight negative potential (- 5V) from the direct current source 33, the secondary electrons generated on the surface of the object 17 to be processed are repelled positively and are returned to the surface of the object 17 to be
20 processed, the surface potential of the object 17 to be processed can be controlled to have about 0 V.

Further, since the plasma generation cell wall 2 which defines the ion source is established to have the negative potential (- 100 V) according to the
25 direct current source 36, even when the multi-aperture

electrodes 32 is given the slight negative potential (- 5V), the ion beam pulled out from the ion source can be repelled and removed completely.

In the foregoing embodiment, the neutralization
5 cell wall 8 defining the neutralization cell 11 and
also serving as a vacuum container has been described.
However, the neutralization cell wall 8 does not
always have to also serve as the vacuum vessel. An
electrode disposed in a vacuum vessel may be used as
10 the neutralization cell wall 8. As the means for
generating a plasma in the neutralization cell 11, the
means for generating a microwave plasma by using the
permanent magnet line 9 and the waveguide 12 has been
described. By using means for generating a high
15 frequency plasma in the neutralization cell 11 or
means for supplying electrons into the neutralization
cell 11 by an electron gun or the like, a similar
effect of flattening the space charge in the
neutralization cell 11 in the invention as that of the
20 foregoing embodiment can be produced.

As stated in above, according to the present
invention, since the ions in charged particles
included in a neutral beam are separated and removed
from the neutral beam by a multi-aperture electrode,
25 and the electrons are separated and removed from the

neutral beam by a multi-pole magnetic field generated by a plurality of magnet lines. Consequently, the charged particles can be removed surely from the neutral beam.

5 Further, according to the present invention, the transmittance can be increased as compared with the technique of using a plurality of electrodes as the charged particle separating means, and the capacity of the neutral beam can be prevented from being decreased.

10 Thus, the capacity of the neutral beam can be increased. Further, by increasing the number of magnet lines with the upsizing of the multi-aperture electrode, the diameter of the neutral beam can be enlarged. Further, since the positive potential to

15 repel the ions is applied to the multi-aperture electrode, a wear due to collision with an ion beam can be avoided. By providing a conductive member as the charged particle separating means, the magnet line can be prevented from being irradiated with the ion

20 beam, so that demagnetization caused by heating the magnet line can be prevented.

Further, according to the present invention, to the process cell wall for defining the process cell, the negative potential is given to the plasma

25 generation cell wall for defining the ion source, the

ion beam pulled out from the ion source can be prevented from centering to the process cell.